L Number	Hits	Search Text	DB	Time stamp
1	0	(((semiconductor or wafer or substrate) and (steam or "water vapor")) and (ozone near10 (gas or vapor or gaseous or mist or fog or atmosphere))) and (nitrogen near10 (gas or vapor or gaseous or mist or fog or atmosphere)) and ((condensing or condensor) near15 (ozone near6 (destroyer or destruct or destroy ot destructor)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/04 12:26
2	0	(((semiconductor or wafer or substrate) and (steam or "water vapor")) and (ozone near10 (gas or vapor or gaseous or mist or fog or atmosphere))) and (nitrogen near10 (gas or vapor or gaseous or mist or fog or atmosphere)) and ((condensing or condensor) near15 (ozone near6 (destroyer or destruct or destroy or destructor)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/04 12:26
3	0	(((semiconductor or wafer or substrate) and (steam or "water vapor")) and (ozone near10 (gas or vapor or gaseous or mist or fog or atmosphere))) and (nitrogen near10 (gas or vapor or gaseous or mist or fog or atmosphere)) and ((condensing or condensor) near15 (ozone near26 (destroyer or destruct or destroy or destructor)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/04 12:27
4	0	((condensing or condensor) near15 (ozone near26 (destroyer or destruct or destroy or destructor)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/04 12:27
5	0	((condensing or condensor) near25 (ozone near26 (destroyer or destruct or destroy or destructor)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/04 12:29
6	1365	(ozone near26 (destroyer or destruct or destroy or destructor))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/04 12:30
7	3	(ozone near26 (destroyer or destruct or destroy or destructor)) same (condensing or condensor)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/04 12:30
8	177	(ozone near26 (destroyer or destruct or destroy or destructor)) and (wafer or semiconductor or substrate)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/04 12:32
9	102	(ozone near26 (destroyer or destruct or destroy or destructor)) and (wafer or semiconductor or substrate) and (cooling or cool or chil or chilling or condense or condensed or condensor or condensing or condenser)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/04 12:33
-	4	(("4778532") or ("5503708") or ("6178973") or ("6582525")).PN.	USPAT	2004/03/02 08:21
-	2	("5896875").PN.	USPAT; EPO; JPO; DERWENT	2004/03/02 08:22
-	2	("6551409").PN.	USPAT; EPO; JPO; DERWENT	2004/03/02 08:52
-	4	(("6276378") or ("6357457") or ("6419408") or ("6496245")).PN.	USPAT	2004/03/02 09:00
-	1	("20030201003").PN.	US-PGPUB	2004/03/02 09:18

—	236	"6178973" and steam and ozone or nitorgen	USPAT	2004/03/02 09:19
—	0	"6178973" and steam and ozone and nitorgen	USPAT	2004/03/02 09:19
—	3	"6178973" and steam and ozone and nitrogen	USPAT	2004/03/02 09:21
—	3	"6178973" and (steam and ozone and nitrogen)	USPAT	2004/03/02 09:31
—	11	((steam near5 (gas or vapor)) and (ozone near5 (gas or vapor)) and (nitrogen near5 gas)) same (wafer or semiconductor or substrate)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/02 10:30
—	10	"4778532" and (steam and ozone and nitrogen)	USPAT	2004/03/02 09:33
—	1	"6491763" and (steam and ozone and nitrogen)	USPAT	2004/03/02 09:34
—	149	((steam or (water near5 vapor)) and (ozone near5 (gas or vapor)) and nitrogen) same (wafer or semiconductor or substrate)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/03 06:32
—	67	219/$.ccls. and "washing machine"	USPAT	2004/03/03 06:42
—	358	68/15.ccls.	USPAT	2004/03/03 08:43
—	391990	(semiconductor or wafer or substrate) and (steam or (water vapor))	USPAT; EPO; JPO; DERWENT	2004/03/03 08:47
—	2508087	semiconductor or wafer or substrate	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/03 08:47
—	474199	(semiconductor or wafer or substrate) and (steam or (water vapor))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/03 09:41
—	4285	((semiconductor or wafer or substrate) and (steam or (water vapor))) and (ozone near10 (gas or vapor or gaseous or mist or fog))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/03 09:47
—	1795	(((semiconductor or wafer or substrate) and (steam or (water vapor))) and (ozone near10 (gas or vapor or gaseous or mist or fog))) and (nitrogen near10 (gas or vapor or gaseous or mist or fog))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/04 11:30
—	272	((((semiconductor or wafer or substrate) and (steam or (water vapor))) and (ozone near10 (gas or vapor or gaseous or mist or fog))) and (nitrogen near10 (gas or vapor or gaseous or mist or fog))) and (134/$.ccls. or 156/$.ccls. 216/$.ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/03 09:36
—	44490	(semiconductor or wafer or substrate) and (steam or "water vapor")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/03 09:35
—	1091	((semiconductor or wafer or substrate) and (steam or "water vapor")) and (ozone near10 (gas or vapor or gaseous or mist or fog))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/03 09:36
—	157	(((semiconductor or wafer or substrate) and (steam or "water vapor")) and (ozone near10 (gas or vapor or gaseous or mist or fog))) and (134/$.ccls. or 156/$.ccls. 216/$.ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/03 09:37

–	.2508087	semiconductor or wafer or substrate	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/03 09:44
–	44490	(semiconductor or wafer or substrate) and (steam or "water vapor")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/03 09:47
–	1255	((semiconductor or wafer or substrate) and (steam or "water vapor")) and (ozone near10 (gas or vapor or gaseous or mist or fog or atmosphere))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/03 09:49
–	739	(((semiconductor or wafer or substrate) and (steam or "water vapor")) and (ozone near10 (gas or vapor or gaseous or mist or fog or atmosphere))) and (nitrogen near10 (gas or vapor or gaseous or mist or fog or atmosphere))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/04 12:12
–	476	((((semiconductor or wafer or substrate) and (steam or "water vapor")) and (ozone near10 (gas or vapor or gaseous or mist or fog or atmosphere))) and (nitrogen near10 (gas or vapor or gaseous or mist or fog or atmosphere))) and ((resist or mask) and (etch or etching or etched) or (washing or wash or clean orcleaning or rinse or rinsing))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/04 09:08
–	7	"5279705" and ozone	USPAT	2004/03/04 07:13
–	14	(("2005180") or ("1857766") or ("4078727") or ("1382633")).PN.	USPAT; EPO; JPO; DERWENT	2004/03/03 11:05
–	0	("0655111").PN.	EPO; JPO; DERWENT	2004/03/03 11:06
–	4	"5302240" and ozone	USPAT	2004/03/04 05:35
–	0	("2003093917").PN.	US-PGPUB	2004/03/04 05:35
–	1	("20030093917").PN.	US-PGPUB	2004/03/04 05:35
–	5	"6239041" and ozone	USPAT	2004/03/04 07:26
–	12	"6240933" and ozone and (steam or "water vapor")	USPAT	2004/03/04 07:27
–	8	"6240933" and ozone and (steam or "water vapor") and nitrogen	USPAT	2004/03/04 07:33
–	1	"6287988" and ozone and (steam or "water vapor") and nitrogen	USPAT	2004/03/04 07:36
–	1	"6290777" and ozone and (steam or "water vapor") and nitrogen	USPAT	2004/03/04 08:07
–	0	"6456372" and ozone and (steam or "water vapor") and nitrogen	USPAT	2004/03/04 08:07
–	3	"6465372" and ozone and (steam or "water vapor") and nitrogen	USPAT	2004/03/04 08:13
–	1	"6482476" and ozone and (steam or "water vapor") and nitrogen	USPAT	2004/03/04 08:15
–	1	"6491763" and ozone and (steam or "water vapor") and nitrogen	USPAT	2004/03/04 08:27
–	1	"6551409" and ozone and (steam or "water vapor") and nitrogen	USPAT	2004/03/04 09:44
–	1	"6568408" and ozone and (steam or "water vapor") and nitrogen	USPAT	2004/03/04 08:46
–	1	"6613692" and ozone and (steam or "water vapor") and nitrogen	USPAT	2004/03/04 09:19

—	5	((((semiconductor or wafer or substrate) and (steam or "water vapor")) and (ozone near10 (gas or vapor or gaseous or mist or fog or atmosphere))) and (nitrogen near10 (gas or vapor or gaseous or mist or fog or atmosphere))) and ((resist or mask) and (etch or etching or etched) or (washing or wash or clean orcleaning or rinse or rinsing))	USOCR	2004/03/04 09:08
—	0	((steam or "water vapor") same (ozone near10 (gas or vapor or gaseous or mist or fog or atmosphere)) same (nitrogen near10 (gas or vapor or gaseous or mist or fog or atmosphere))) same ((ratio or ratios or concentration or concentrations) near25 (control or controller or microporcessor or cpu))	USOCR	2004/03/04 09:10
—	2	((steam or "water vapor") same (ozone near10 (gas or vapor or gaseous or mist or fog or atmosphere)) same (nitrogen near10 (gas or vapor or gaseous or mist or fog or atmosphere))) same ((ratio or ratios or concentration or concentrations) near25 (control or controller or microporcessor or cpu))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/04 09:11
—	221	((steam or "water vapor") and (ozone near10 (gas or vapor or gaseous or mist or fog or atmosphere)) and (nitrogen near10 (gas or vapor or gaseous or mist or fog or atmosphere))) and ((ratio or ratios or concentration or concentrations) near25 (control or controller or microporcessor or cpu))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/04 09:12
—	1	"6588437" and ozone and (steam or "water vapor") and nitrogen	USPAT	2004/03/04 09:29
—	1	"6588437" and nitrogen	USPAT	2004/03/04 09:29
—	1	"6235112" and ozone and (steam or "water vapor") and nitrogen	USPAT	2004/03/04 10:57
—	3	"5896875" and ozone and (steam or "water vapor") and nitrogen	USPAT	2004/03/04 10:03
—	14	"bergman" and ozone and (steam or "water vapor") and nitrogen	USPAT	2004/03/04 10:40
—	20	"4749440" and ozone and (steam or "water vapor") and nitrogen	USPAT	2004/03/04 10:11
—	66	"4749440" and (steam or "water vapor") and nitrogen	USPAT	2004/03/04 10:36
—	305	halogen near5 ozone	USPAT	2004/03/04 10:17
—	125	(halogen near5 ozone) and (wafer or semiconductor or substrate)	USPAT	2004/03/04 10:20
—	113	(("HF" or "hydrogen fluoride" or anhydrous) near5 ozone) and (wafer or semiconductor or substrate)	USPAT	2004/03/04 10:24
—	22	((anhydrous) near5 ozone) and (wafer or semiconductor or substrate)	USPAT	2004/03/04 10:24
—	0	"548596" and (steam or "water vapor") and nitrogen and ozone	EPO; DERWENT	2004/03/04 11:05
—	0	"0548596" and (steam or "water vapor") and nitrogen and ozone	EPO; DERWENT	2004/03/04 10:37
—	0	"0548596" and (steam or "water vapor") and ozone	EPO; DERWENT	2004/03/04 10:37
—	0	"0548596" and ozone	EPO; DERWENT	2004/03/04 10:38
—	2	"0548596"	EPO; DERWENT	2004/03/04 10:38
—	6	"548596"	EPO; DERWENT	2004/03/04 10:38
—	3	"548596" and ozone	EPO; DERWENT	2004/03/04 10:39
—	0	"548596" and ozone and nitrogen	EPO; DERWENT	2004/03/04 10:39

–	3	"548596" and ozone and water	EPO; DERWENT	2004/03/04 10:39
–	1	"5964954" and ozone and (steam or "water vapor") and nitrogen	USPAT	2004/03/04 10:41
–	3	"5378317" and ozone and (steam or "water vapor") and nitrogen	USPAT	2004/03/04 10:48
–	1	"6551409" and ozone and (steam or "water vapor") and nitrogen	USPAT	2004/03/04 10:50
–	1	"6551409" and nitrogen	USPAT	2004/03/04 10:50
–	1	"6588437" and ozone and (steam or "water vapor") and nitrogen	USPAT	2004/03/04 10:58
–	0	"65239041" and ozone and (steam or "water vapor") and nitrogen	USPAT	2004/03/04 10:51
–	5	"6239041" and ozone and (steam or "water vapor") and nitrogen	USPAT	2004/03/04 10:52
–	1	"6235112" and ozone and (steam or "water vapor") and nitrogen	USPAT	2004/03/04 10:53
–	1	"6235112" and ozone and (steam or "water vapor")	USPAT	2004/03/04 10:56
–	1	"6235112" and ozone and nitrogen	USPAT	2004/03/04 10:56
–	2	"6235112" and ozone	USPAT	2004/03/04 10:57
–	1	"6588437" and (steam or "water vapor")	USPAT	2004/03/04 11:05
–	2	"6551409" and (steam or "water vapor")	USPAT	2004/03/04 11:05
–	0	"6551409" and (steam or "water vapor") and nitrogen and ozone	EPO; DERWENT	2004/03/04 11:27
–	0	"6551409" and (steam or "water vapor") and ozone	EPO; DERWENT	2004/03/04 11:06
–	1	"6551409" and (steam or "water vapor" or "water vapour") and ozone	EPO; DERWENT	2004/03/04 11:06
–	0	"6551409" and (steam or "water vapor" or "water vapour") and ozone and nitrogen	EPO; DERWENT	2004/03/04 11:12
–	76	("acid gas" or "acid gases") near10 ozone	USPAT; EPO; JPO; DERWENT	2004/03/04 11:13
–	1	"4749440" and ozone	EPO; DERWENT	2004/03/04 11:29
–	79	(semiconductor or wafer or substrate) and ((ozone near10 (vapour or gas or vapor or gaseous or mist or fog or atmosphere)) near15 (("HF" or "hydrogen fluoride") near10 (gas or vapor or gaseous or mist or fog or atmosphere)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/04 11:37